

**Amendments to the Claims:**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1-11. (Canceled)

12. (Previously Presented) An exposure apparatus that exposes a substrate via a liquid, comprising:

a nozzle member comprising at least any one of a supply outlet that supplies a liquid and a collection inlet that collects a liquid;

a support member that supports the nozzle member; and

an adjustment mechanism that adjusts a positional relationship between the support member and the nozzle member.

13. (Original) An exposure apparatus as recited in Claim 12,

wherein the adjustment mechanism comprises a drive apparatus that drives the nozzle member with respect to the support member.

14. (Original) An exposure apparatus as recited in Claim 13, comprising:

a position measuring instrument that measures the positional relationship between the support member and the nozzle member;

wherein, the drive apparatus drives based on a measurement result of the position measuring instrument.

15. (Previously Presented) An exposure apparatus as recited in Claim 12, comprising:

an optical system;

wherein, the optical system is supported by the support member.

16. (Previously Presented) An exposure apparatus that exposes a substrate via an optical system and a liquid, comprising:

a nozzle member supported by a prescribed support member, and comprising at least any one of a supply outlet that supplies a liquid and a collection inlet that collects a liquid; and

an adjustment mechanism that adjusts a positional relationship between the optical system and the nozzle member.

17. (Original) An exposure apparatus as recited in Claim 16,

wherein the optical system is supported by the support member; and the adjustment mechanism comprises a drive apparatus that drives the nozzle member with respect to the support member.

18. (Original) An exposure apparatus as recited in Claim 17, comprising:

a position measuring instrument that measures the positional relationship between the optical system and the nozzle member;

wherein, the drive apparatus drives based on a measurement result of the position measuring instrument.

19. (Previously Presented) An exposure apparatus that exposes a substrate via a liquid, comprising:

a nozzle member supported by a prescribed support member, and comprising at least any one of a supply outlet that supplies a liquid and a collection inlet that collects a liquid;

a substrate stage that holds the substrate; and

an adjustment mechanism that comprises a drive apparatus that drives the nozzle member with respect to the support member, and that adjusts a positional relationship between the substrate stage and the nozzle member.

20. (Original) An exposure apparatus as recited in Claim 19, comprising:  
a position measuring instrument that measures the positional relationship  
between the substrate stage and the nozzle member;  
wherein, the drive apparatus drives based on a measurement result of the  
position measuring instrument.
21. (Previously Presented) An exposure apparatus that exposes a substrate via a  
liquid, comprising:  
a nozzle member that comprises at least any one of a supply outlet that  
supplies a liquid and a collection inlet that collects a liquid;  
wherein, at least one part of the nozzle member is movable in an optical axis  
direction of an exposure light that exposes the substrate.
22. (Original) An exposure apparatus as recited in Claim 21, comprising:  
at least one position measuring instrument that detects information related to a  
position of the nozzle member;  
wherein, the position of the nozzle member is controlled based on a  
measurement result of the position measuring instrument.
23. (Original) An exposure apparatus as recited in Claim 22,  
wherein the position of the nozzle member is controlled based on information  
related to the liquid.
24. (Canceled)